



## The Fine Line : VIDEOS FOR THE EBEAM COMMUNITY Spring 2014

### Shot Talk - A Word from our Sponsor

Aki Fujimura, CEO of D2S, reviews the latest buzz at the SPIE Advanced Lithography Conference—including EUV, DSA and mask shot count reduction efforts—as well as previews Photomask Japan and its importance to the global mask supply ecosystem.



### From the White Board

Aki Fujimura dons his lecturer's cap and describes the growing danger posed by mask hotspots as well as how model-based simulation finds mask hotspots before they escape the mask shop.

*[Click here to watch this video in Japanese](#)*



### Tech Talk

Naoya Hayashi of DNP looks at the latest trends and challenges with mask writing, and highlights the results of DNP's evaluation of model-based mask data preparation (MB-MDP) in reducing mask shot count with equal pattern quality compared to conventional MDP approaches.



### Perspectives

Mark Sheppard of Advantest describes emerging trends in mask metrology to tackle mask hotspots and offers his perspective on the most critical issue the eBeam community should tackle in the coming years. Spoiler alert—it's not EUV!



### VIDEO ARCHIVE

#### The Fine Line Autumn 2013 Edition



Shot Talk: Aki Fujimura of D2S



From the White Board:  
Ryan Pearman



Tech Talk: Dr. Kokoro Kato of  
Hitachi High-Tech Science Corp.



Perspectives: Brian Grenon

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